

## Supporting Information

# Enhanced Photoelectrochemical Performance of Quantum Dot-Sensitized TiO<sub>2</sub> Nanotube Arrays with Al<sub>2</sub>O<sub>3</sub> overcoating by Atomic Layer Deposition

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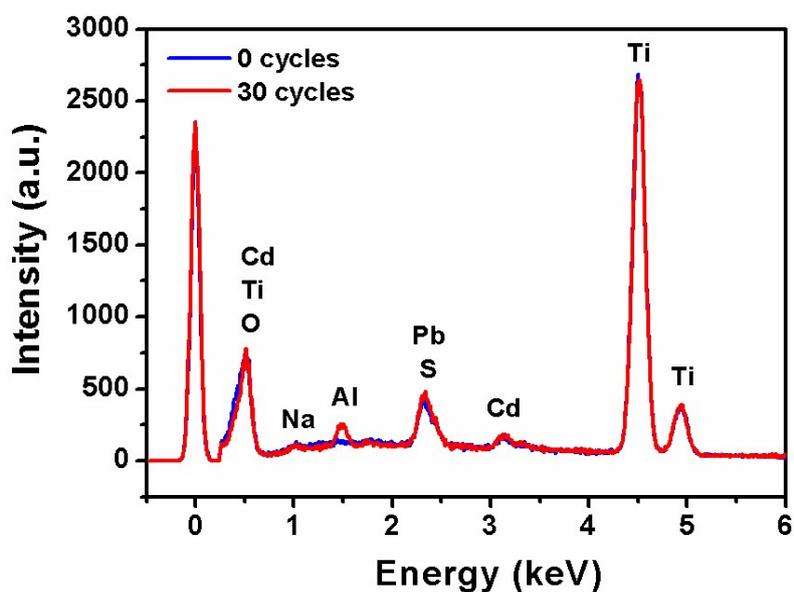
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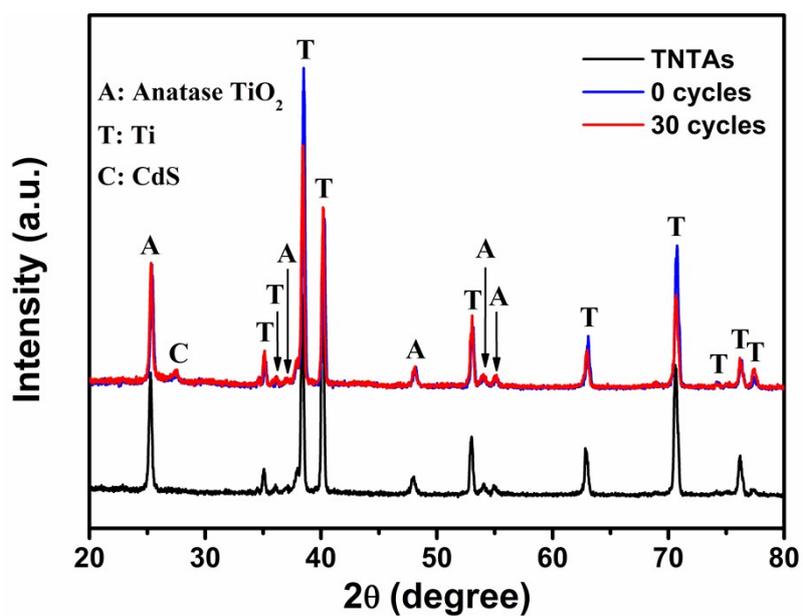
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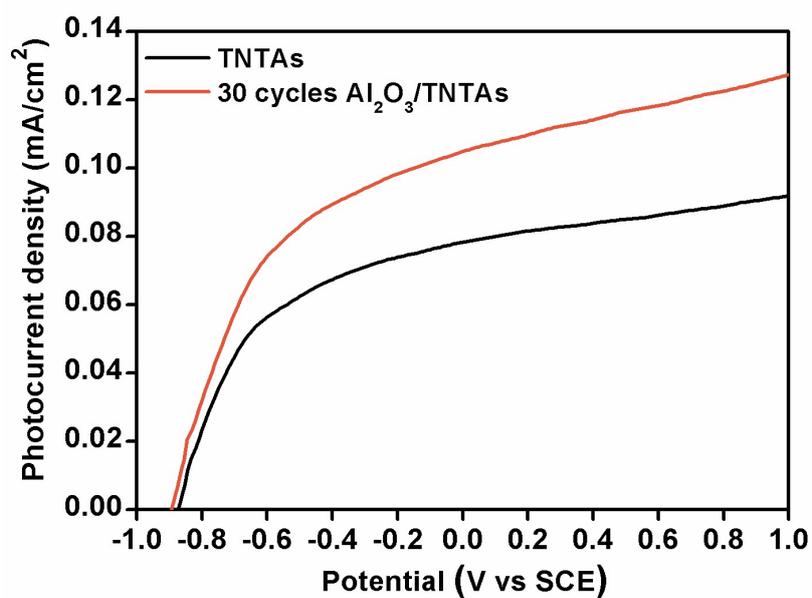
**Fig. S1.** EDS results of quantum dot-sensitized TiO<sub>2</sub> nanotube arrays without Al<sub>2</sub>O<sub>3</sub> deposition (blue) and with 30 ALD cycles of Al<sub>2</sub>O<sub>3</sub> overlayer (red). Na comes from the Na<sub>2</sub>S used as the precursor.

**Table S1.** Atomic percentages of the elements derived from the EDS spectra in Fig. S1.

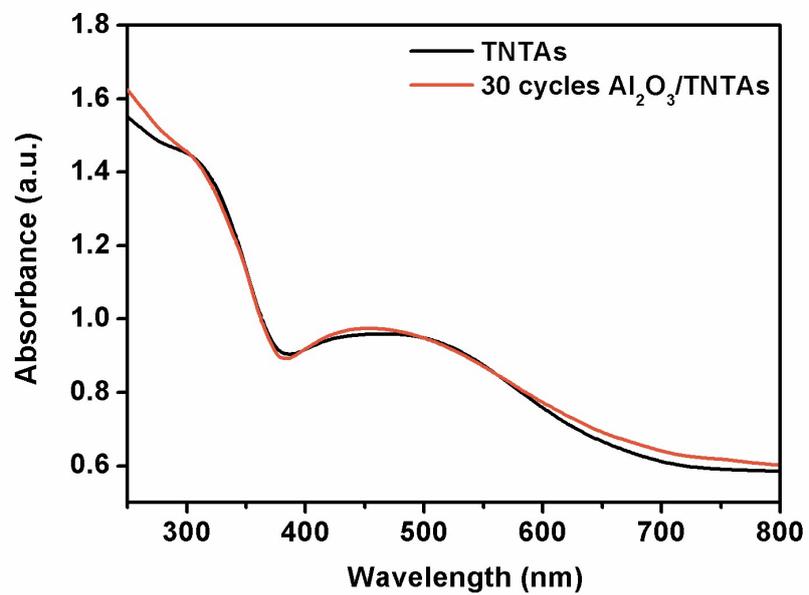
Photoanodes	Ti	O	Al	Na	Pb	Cd	S
0 cycles [%]	32.72	64.82	0.00	0.41	0.47	0.52	1.06
30 cycles [%]	35.07	62.19	0.67	0.00	0.45	0.44	1.17



**Fig. S2.** XRD patterns of pure TiO<sub>2</sub> nanotube arrays (TNTAs, black), quantum dot-sensitized TiO<sub>2</sub> nanotube arrays without Al<sub>2</sub>O<sub>3</sub> deposition (blue) and with 30 ALD cycles of Al<sub>2</sub>O<sub>3</sub> overlayer (red).



**Fig. S3.** Linear sweep voltammograms measured from pure TiO<sub>2</sub> nanotube arrays without Al<sub>2</sub>O<sub>3</sub> deposition (TNTAs, black) and with 30 ALD cycles of Al<sub>2</sub>O<sub>3</sub> (orange) under simulated solar illumination (100 mW cm<sup>-2</sup>, AM 1.5 G) at a scan rate of 10 mV s<sup>-1</sup>.



**Fig. S4.** UV-visible absorption spectra of the pure TiO<sub>2</sub> nanotube arrays without Al<sub>2</sub>O<sub>3</sub> deposition (TNTAs, black) and with 30 ALD cycles of Al<sub>2</sub>O<sub>3</sub> overlayer (orange).

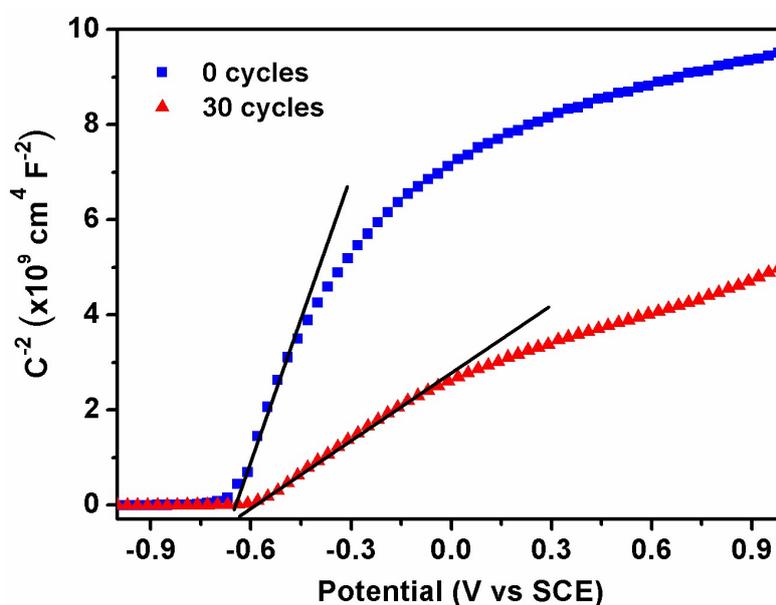
### Mott-Schottky analysis of photoanode:

The Mott-Schottky analysis was performed on quantum dot-sensitized TiO<sub>2</sub> nanotube arrays before and after Al<sub>2</sub>O<sub>3</sub> deposition at a fixed frequency of 800 Hz with a perturbation amplitude of 10 mV and a scan rate of 30 mV s<sup>-1</sup>. The electrolyte was 0.1 M Na<sub>2</sub>SO<sub>4</sub> aqueous solution.

The Mott-Schottky equation correlates the inverse of the square capacitance with the donor density,  $N_D$ , and the flat band potential,  $V_{FB}$ , starting from Poisson's equation coupled with Boltzmann's distribution to describe the distribution of charges in the space charge region and Gauss' law relating the electric field at the interface [S1]. The Mott-Schottky equation is described by [S2]:

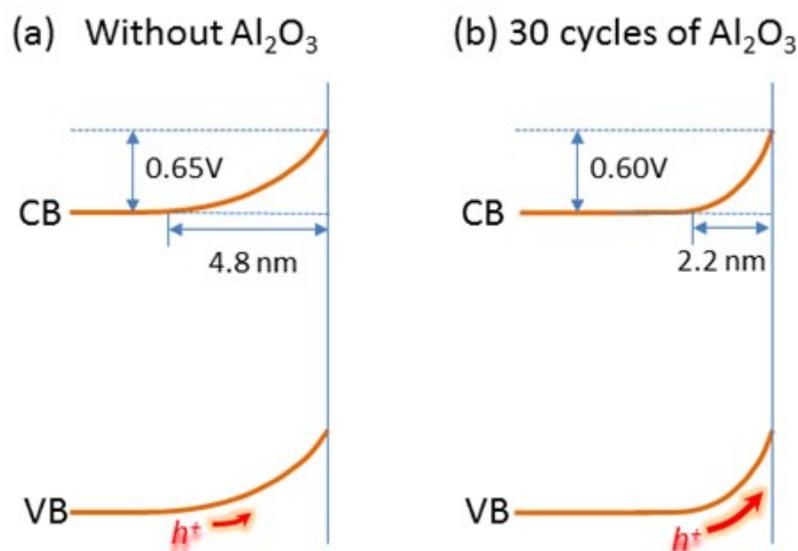
$$\frac{1}{C^2} = \left( \frac{2}{e\epsilon_0\epsilon_s N_D} \right) \left[ (V - V_{FB}) - \frac{k_B T}{e} \right]$$

where  $C$  is the space charge capacitance in the semiconductor,  $e$  is the elemental charge constant,  $\epsilon_0$  is the permittivity of free space,  $\epsilon_s$  is the dielectric constant of the semiconductor,  $V$  is the applied potential,  $k_B$  is the Boltzmann constant, and  $T$  is the absolute temperature. The Mott-Schottky analysis of the space charge capacitance is performed in the linear region of the  $C^{-2}$  vs potential plot. A dielectric constant  $\epsilon = 48$  for TiO<sub>2</sub> is used to extract the flat band potential and the donor density of the photoanode without Al<sub>2</sub>O<sub>3</sub> deposition (blue squares in Fig. S5) and the photoanode with 30 ALD cycles of Al<sub>2</sub>O<sub>3</sub> overlayer (red triangles in Fig. S5) [S3].



**Fig. S5.** Mott-Schottky analysis of quantum dot-sensitized TiO<sub>2</sub> nanotube arrays without Al<sub>2</sub>O<sub>3</sub> deposition (blue squares) and with 30 ALD cycles of

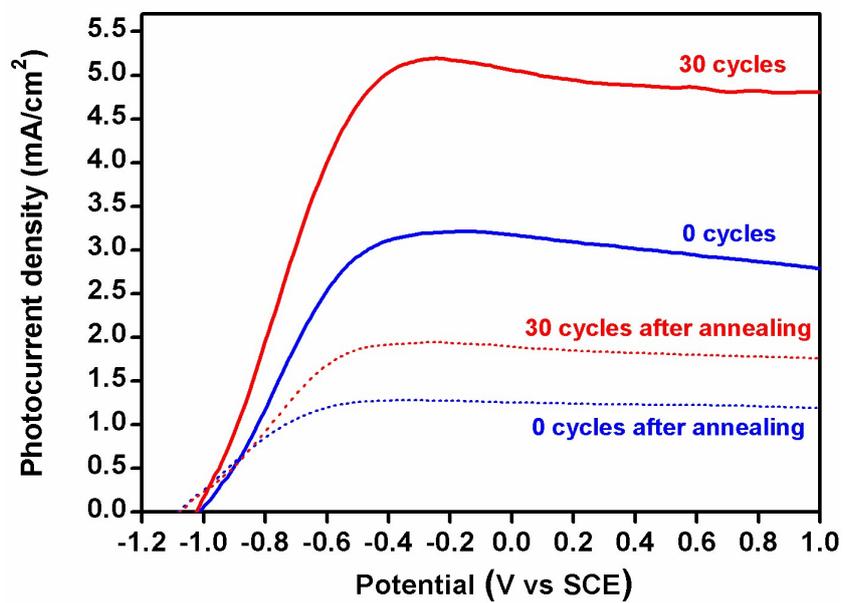
Al<sub>2</sub>O<sub>3</sub> overlayer (red triangles). The inverse of the square space charge capacitance is plotted vs the potential applied during the impedance measurement.



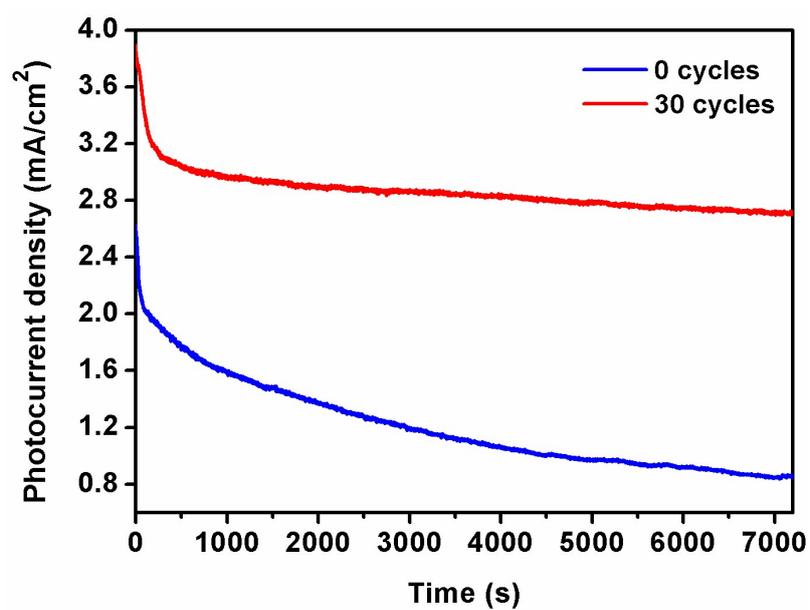
**Fig. S6.** Schematic band diagrams near surface based on the calculated electronic parameters for the photoelectrodes (a) without Al<sub>2</sub>O<sub>3</sub> deposition and (b) with 30 ALD cycles of Al<sub>2</sub>O<sub>3</sub> overlayer. The size of the arrow presents the strength of the effect from built-in electric field.

**Table S2.** EIS fitting results.

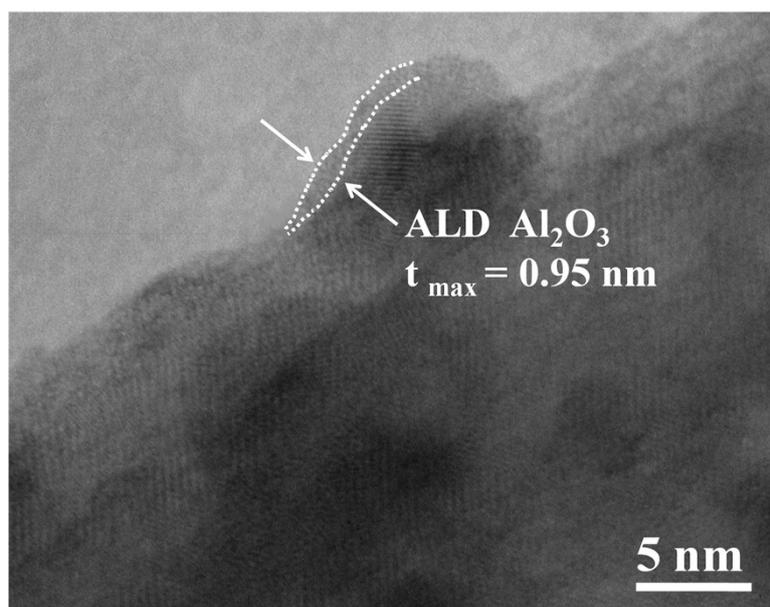
Photoanode	$R_s/\Omega$	$R_{ct}/\Omega$	CPE/F
0 cycles	9.0	207.8	$1.9 \times 10^{-3}$
30 cycles	8.8	145.0	$2.4 \times 10^{-3}$



**Fig. S7.** Photocurrent density-potential curves of quantum dot-sensitized TiO<sub>2</sub> nanotube arrays with 0 cycles (blue) and 30 cycles (red) of Al<sub>2</sub>O<sub>3</sub> overlayer before (solid lines) and after (dot lines) annealing at 400 °C.



**Fig. S8.** Time-dependence photocurrent density of the quantum dot-sensitized TiO<sub>2</sub> nanotube array photoelectrodes without Al<sub>2</sub>O<sub>3</sub> deposition (blue) and with 30 ALD cycles of Al<sub>2</sub>O<sub>3</sub> overlayer (red).



**Fig. S9.** High-resolution TEM image of quantum dot-sensitized  $\text{TiO}_2$  nanotube arrays with 30 ALD cycles of  $\text{Al}_2\text{O}_3$  overlayer after PEC test.

## References

[S1] F. Le Formal, N. Tétreault, M. Cornuz, T. Moehl, M. Grätzel, K. Sivula, *Chem. Sci.* 2 (2011) 737-743.

[S2] A. Wolcott, W. A. Smith, T. R. Kuykendall, Y. Zhao, J. Z. Zhang, *Adv. Funct. Mater.* 19 (2009) 1849-1856.

[S3] M. Ye, J. Gong, Y. Lai, C. Lin, Z. Lin, *J. Am. Chem. Soc.* 134 (2012) 15720-15723.